

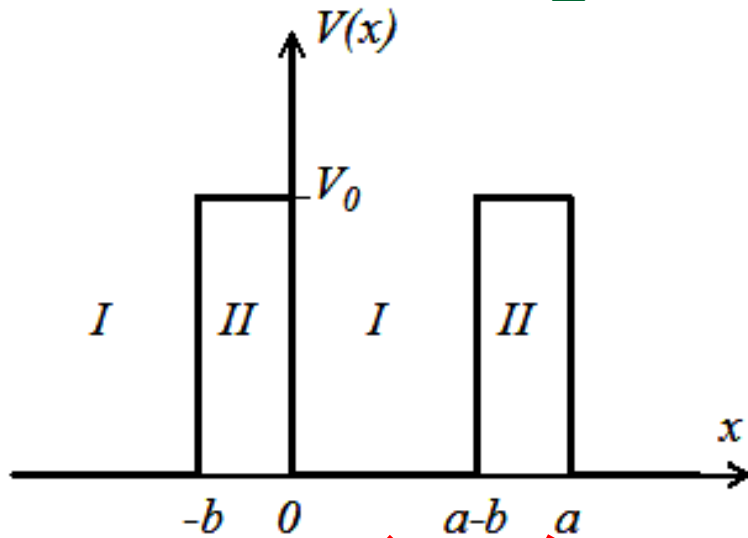
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# Solid State Detectors - Physics

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# The Kronig-Penney model



$$\left( -\frac{\hbar^2}{2m} \frac{d^2}{dx^2} + V[x] \right) \psi = E \psi$$

$$\frac{d^2 \psi}{dx^2} + \frac{2m}{\hbar^2} (E - V_0) \psi = 0$$

$$\frac{d^2 \psi}{dx^2} + \frac{2m}{\hbar^2} E \psi = 0$$

# Bloch's theorem

- Assuming that the solution is a Bloch function

$$\Psi(x) = u(x)e^{ikx}$$

and  $u(x)$  has the periodicity of the potential

- Schrödinger's equation becomes:

$$\frac{d^2 u_I(x)}{dx^2} + 2ik \frac{du_I(x)}{dx} + (\beta^2 - k^2)u_I(x) = 0 \text{ for } 0 < x < a-b$$

$$\beta = \frac{\sqrt{2mE}}{\hbar}$$

$$\frac{d^2 u_{II}(x)}{dx^2} + 2ik \frac{du_{II}(x)}{dx} - (k^2 + \alpha^2)u_{II}(x) = 0 \text{ for } a-b < x < a$$

$$\alpha = \frac{\sqrt{2m(V_0 - E)}}{\hbar}$$

# Solving...

- Solutions

$$u_I(x) = (A \cos \beta x + B \sin \beta x) e^{-\alpha x} \text{ for } 0 < x < a-b$$

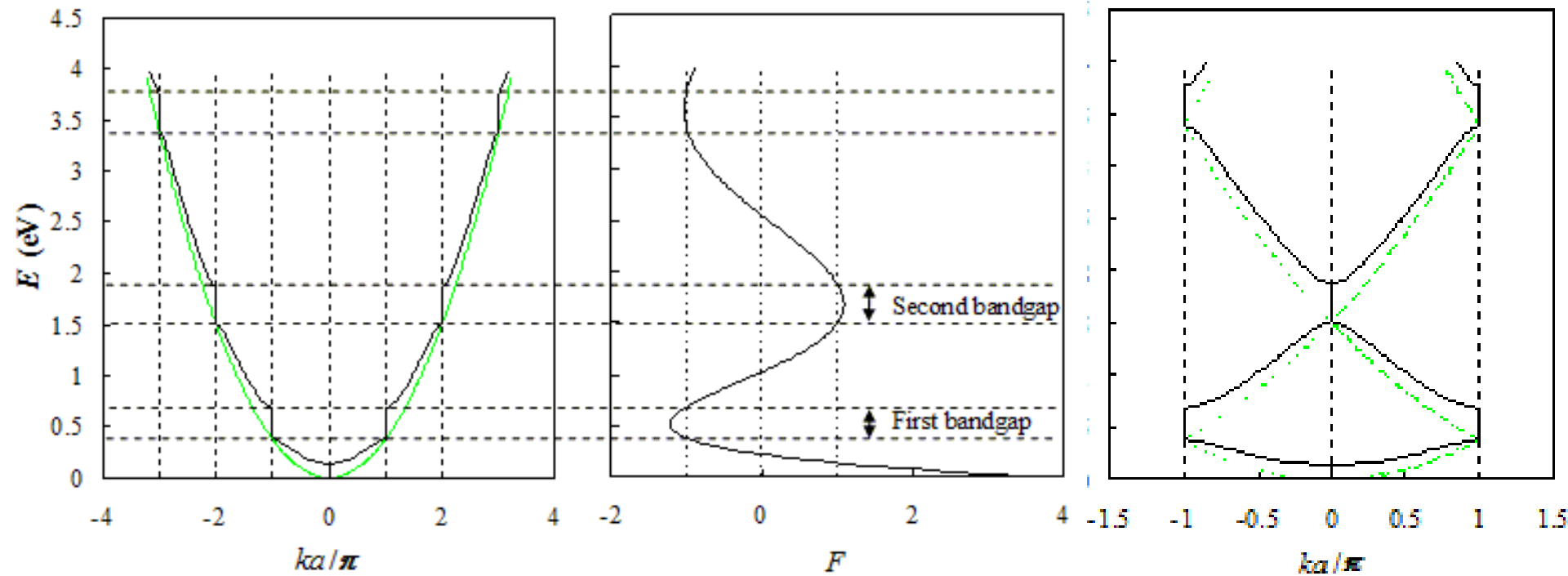
$$u_{II}(x) = (C \cosh \alpha x + D \sin \alpha x) e^{-i\beta x} \text{ for } a-b < x < a$$

- By continuity of the functions and derivatives

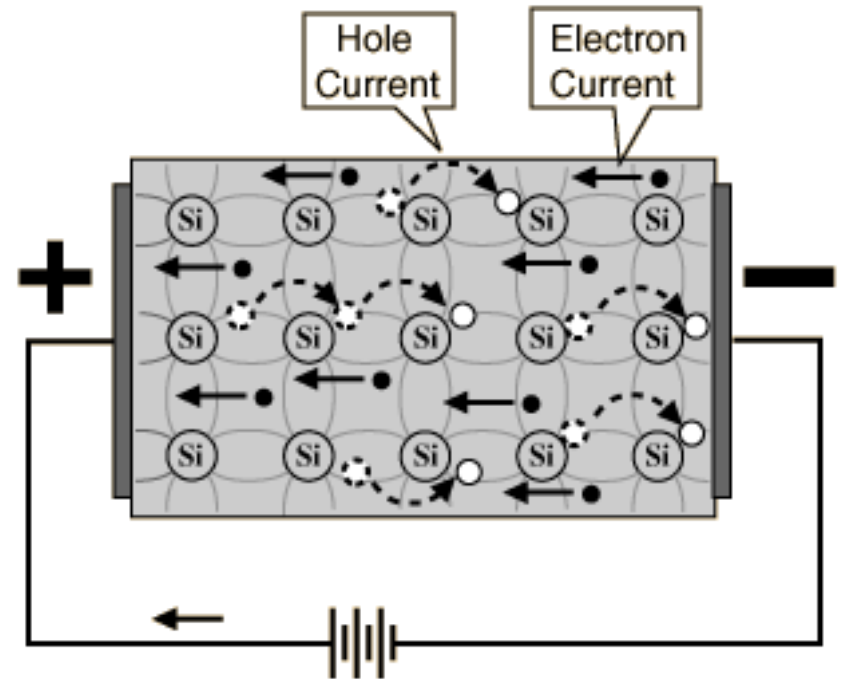
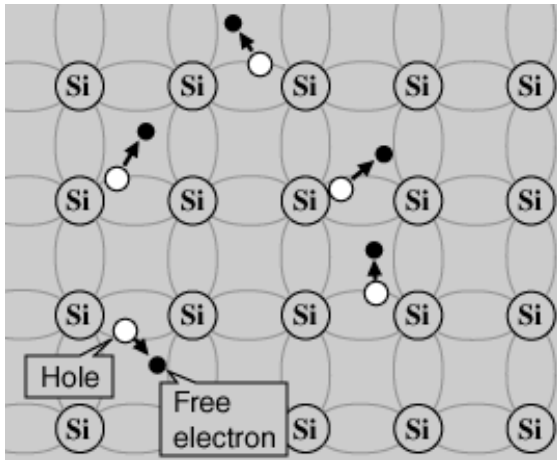
$$\cos ka = F = \frac{\alpha^2 - \beta^2}{2\alpha\beta} \sinh \alpha b \sin \beta(a-b) + \cosh \alpha b \cos \beta(a-b)$$

Transcendental equation → numerical solution

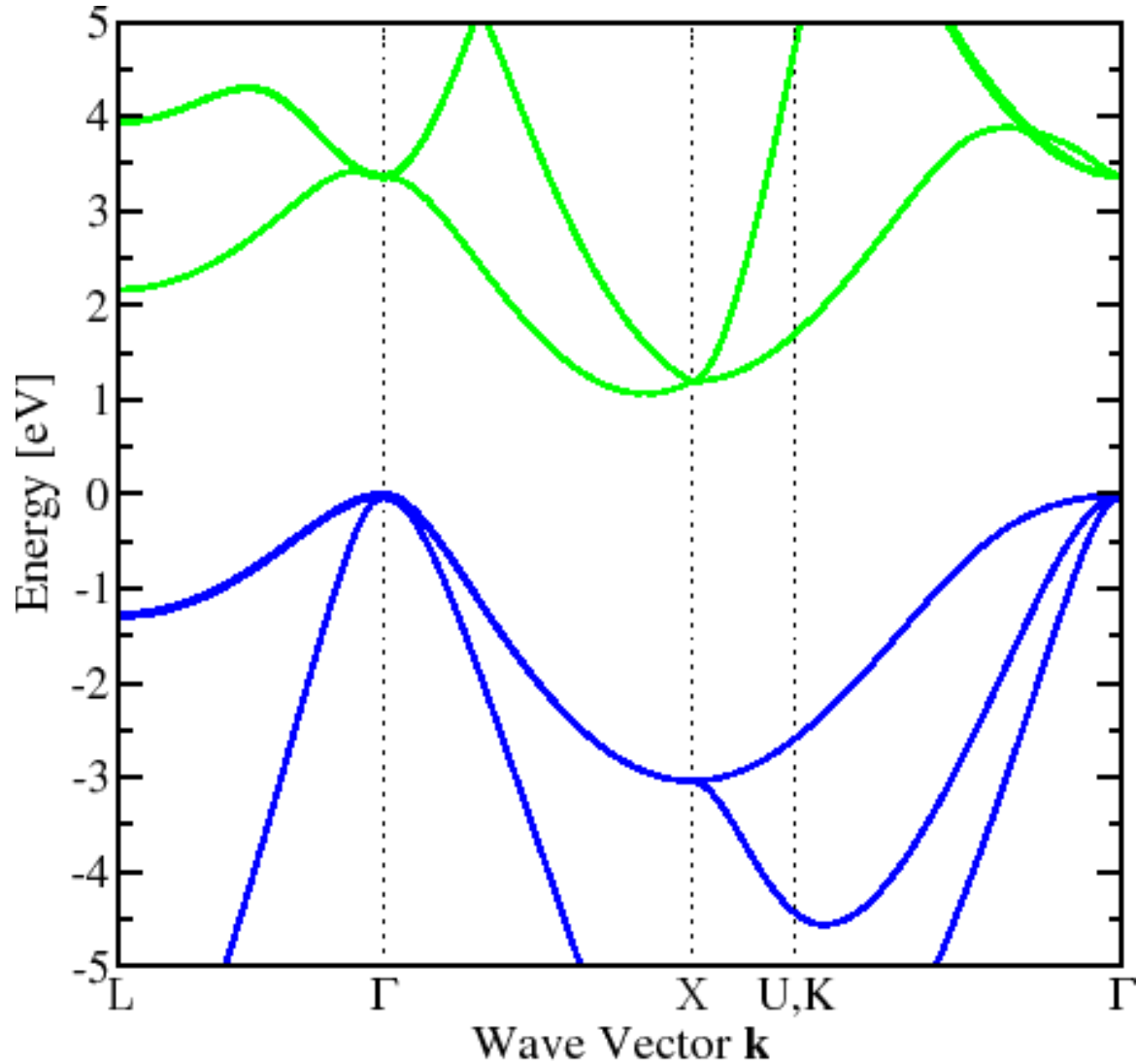
# Band Structure



# Si Intrinsic Semiconductor



# Si Band Structure



# Semiconductor BandGap

- Indirect

$$\alpha \propto \frac{(h\nu - E_g + E_p)^2}{\exp(\frac{E_p}{kT}) - 1} + \frac{(h\nu - E_g - E_p)^2}{1 - \exp(-\frac{E_p}{kT})}$$

- Direct

$$\alpha \approx A^* \sqrt{h\nu - E_g}$$

$$A^* = \frac{q^2 x_{vc}^2 (2m_r)^{3/2}}{\lambda_0 \epsilon_0 \hbar^3 n}$$

$$m_r = \frac{m_h^* m_e^*}{m_h^* + m_e^*}$$



# Carrier density

- Fermi-dirac distribution ( $\mu$  in semiconductors is  $E_F$ )

$$f(E) = \frac{1}{\text{Exp}[(E - \mu) / k_B T] + 1}$$

- Density of states in the conduction band

$$g(E) = \frac{V}{2\pi^2 \hbar^3} (2m_e)^{3/2} (E - E_g)^{1/2}$$

- Density of states in the valence band

$$g(E) = \frac{V}{2\pi^2 \hbar^3} (2m_h)^{3/2} (-E)^{1/2}$$

# Carrier density

- Electron density in the Conduction Band

$$\begin{aligned}n &= \frac{N}{V} = \frac{1}{V} \int_{E_c}^{\infty} f(E) g(E) dE \\&= \frac{(2m_e)^{3/2}}{2\pi^2 \hbar^3} \int e^{-(E-\mu)/k_B T} (E - E_f)^{1/2} dE \\&= 2 \left( \frac{2\pi m_e k_B T}{\hbar^2} \right)^{3/2} e^{-(\mu - E_c)/k_B T}\end{aligned}$$

- Similarly, to holes in the Valence Band

$$p = 2 \left( \frac{2\pi m_h k_B T}{\hbar^2} \right)^{3/2} e^{-\mu/k_B T}$$

# Carrier density

- Finally

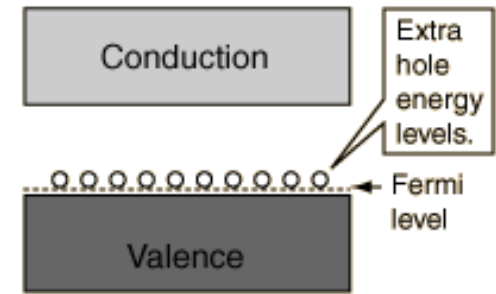
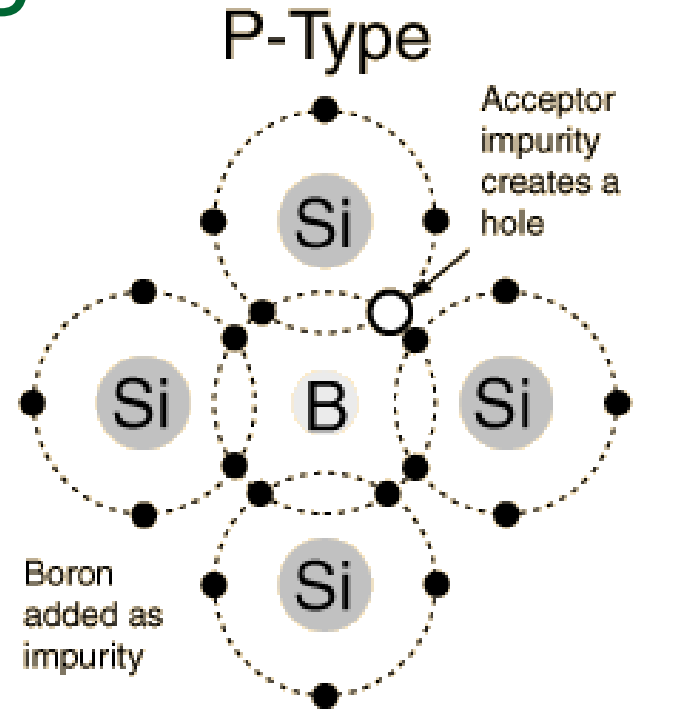
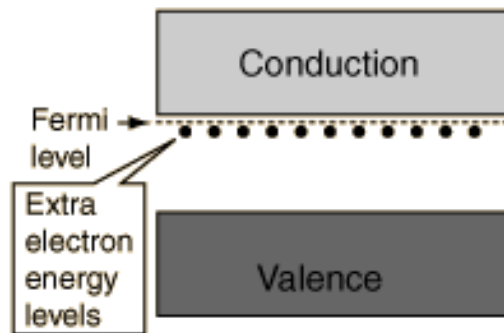
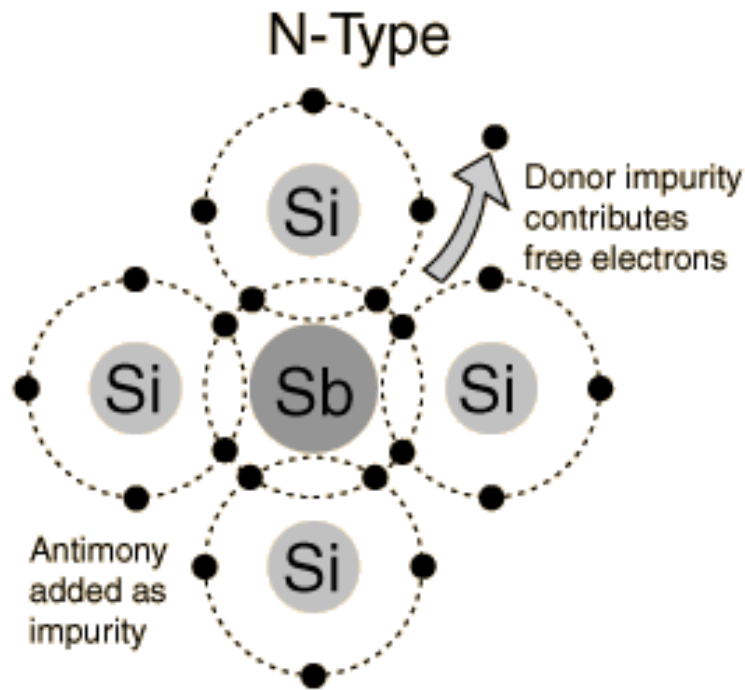
$$np = n_i^2 = N_c N_v e^{-E_g / k_B T}$$

$$N_c = 2 \left( \frac{2 \pi m_e k_B T}{\hbar^2} \right)^{3/2}$$
$$N_v = 2 \left( \frac{2 \pi m_h k_B T}{\hbar^2} \right)^{3/2}$$

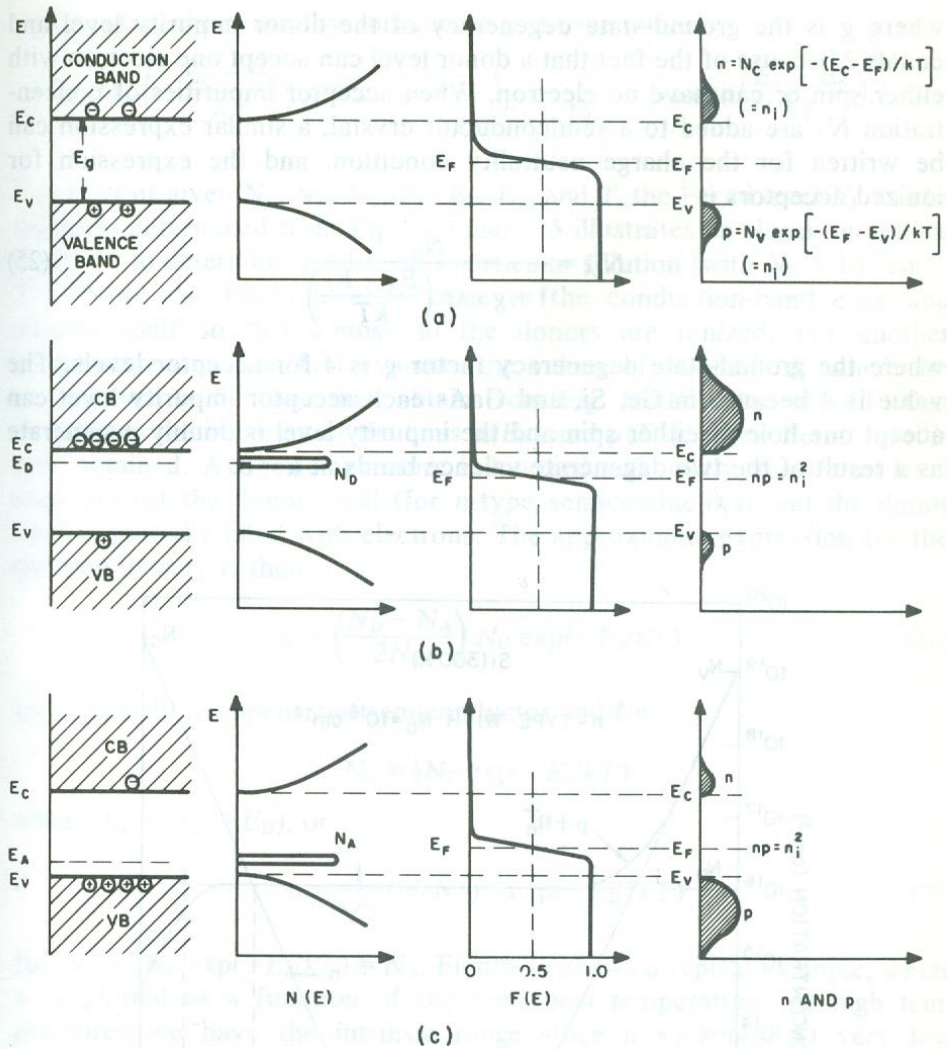
- And since  $n=p=n_i$

$$E_i = \frac{E_C + E_V}{2} + \frac{3}{4} kT \ln \left( \frac{m_h^*}{m_e^*} \right)$$

# n- and p-type doping



# Density of States



# Introducing impurities

- Donors  $n = N_D^+ + p$  (neutrality)

$$N_D^+ = N_D \left[ 1 - \frac{1}{1 + \frac{1}{g} \exp\left(\frac{E_D - E_F}{kT}\right)} \right]$$

$$N_C \exp\left(-\frac{E_C - E_F}{kT}\right) = N_D \frac{1}{1 + 2 \exp\left(\frac{E_F - E_D}{kT}\right)} + N_V \exp\left(\frac{E_V - E_F}{kT}\right)$$

- Acceptors

$$N_A^- = \frac{N_A}{1 + g \exp\left(\frac{E_A - E_F}{kT}\right)}$$

# Extrinsic Semiconductors

- **n-type** (nondegenerated)

$$n_{no} = \frac{1}{2} \left[ (N_D - N_A) + \sqrt{(N_D - N_A)^2 + 4n_i^2} \right]$$
$$\approx N_D \quad \text{if } |N_D - N_A| \gg n_i \quad \text{and} \quad N_D \gg N_A$$

$$p_{no} = n_i^2 / n_{no} \approx n_i^2 / N_D$$

$$E_C - E_F = kT \ln \left( \frac{N_C}{N_D} \right) \quad E_F - E_i = kT \ln \left( \frac{n_{no}}{n_i} \right)$$

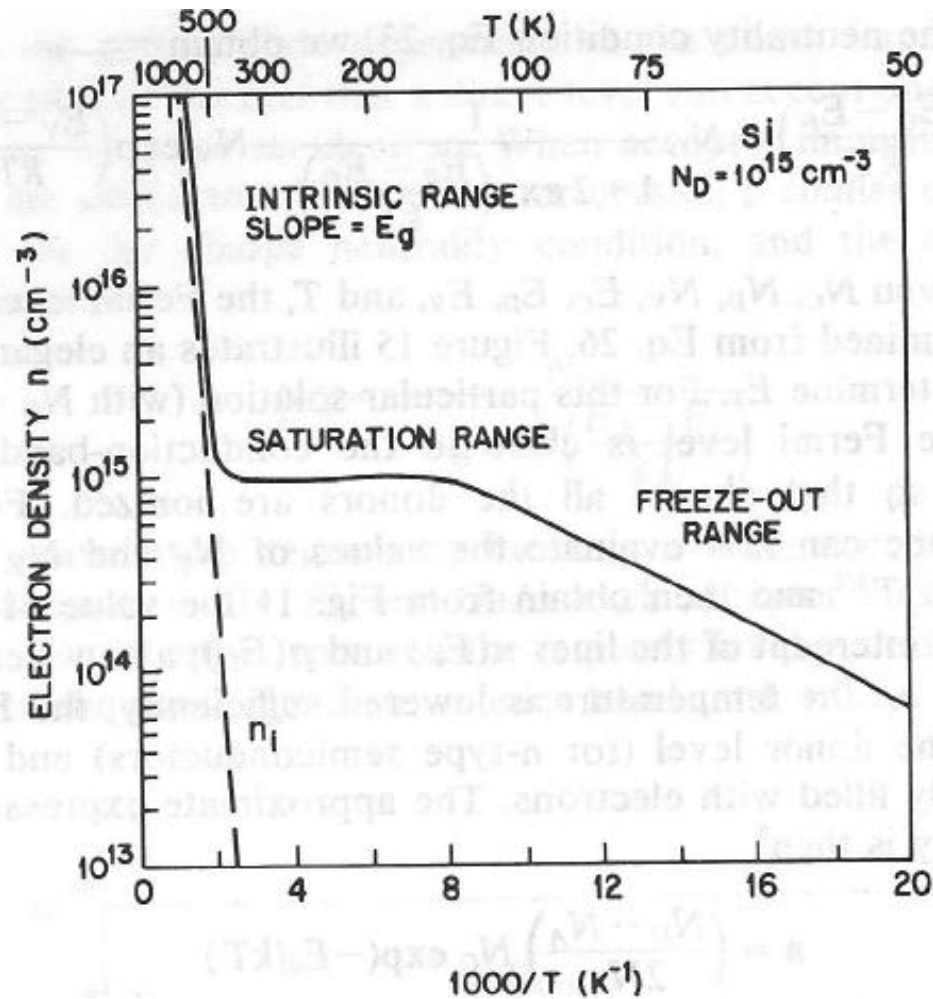
- **p-type** (nondegenerated)

$$p_{po} = \frac{1}{2} \left[ (N_A - N_D) + \sqrt{(N_A - N_D)^2 + 4n_i^2} \right]$$
$$\approx N_A \quad \text{if } |N_A - N_D| \gg n_i \quad \text{and} \quad N_A \gg N_D$$

$$n_{po} = n_i^2 / p_{po} \approx n_i^2 / N_A$$

$$E_F - E_V = kT \ln \left( \frac{N_V}{N_A} \right) \quad E_i - E_F = kT \ln \left( \frac{p_{po}}{n_i} \right)$$

# n-type semiconductor

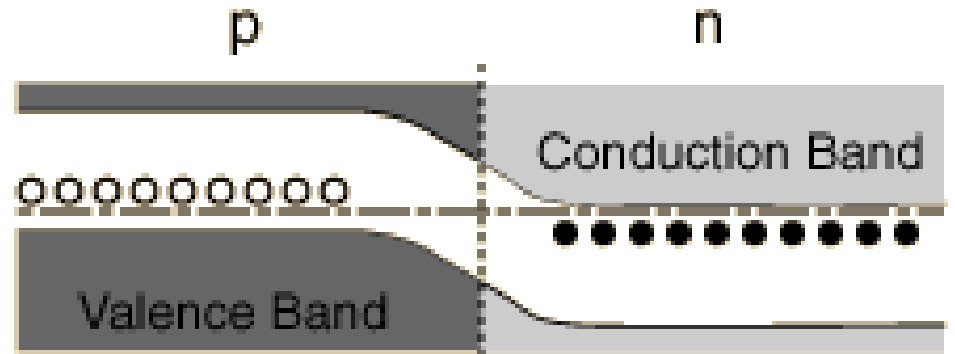




# PN Junction

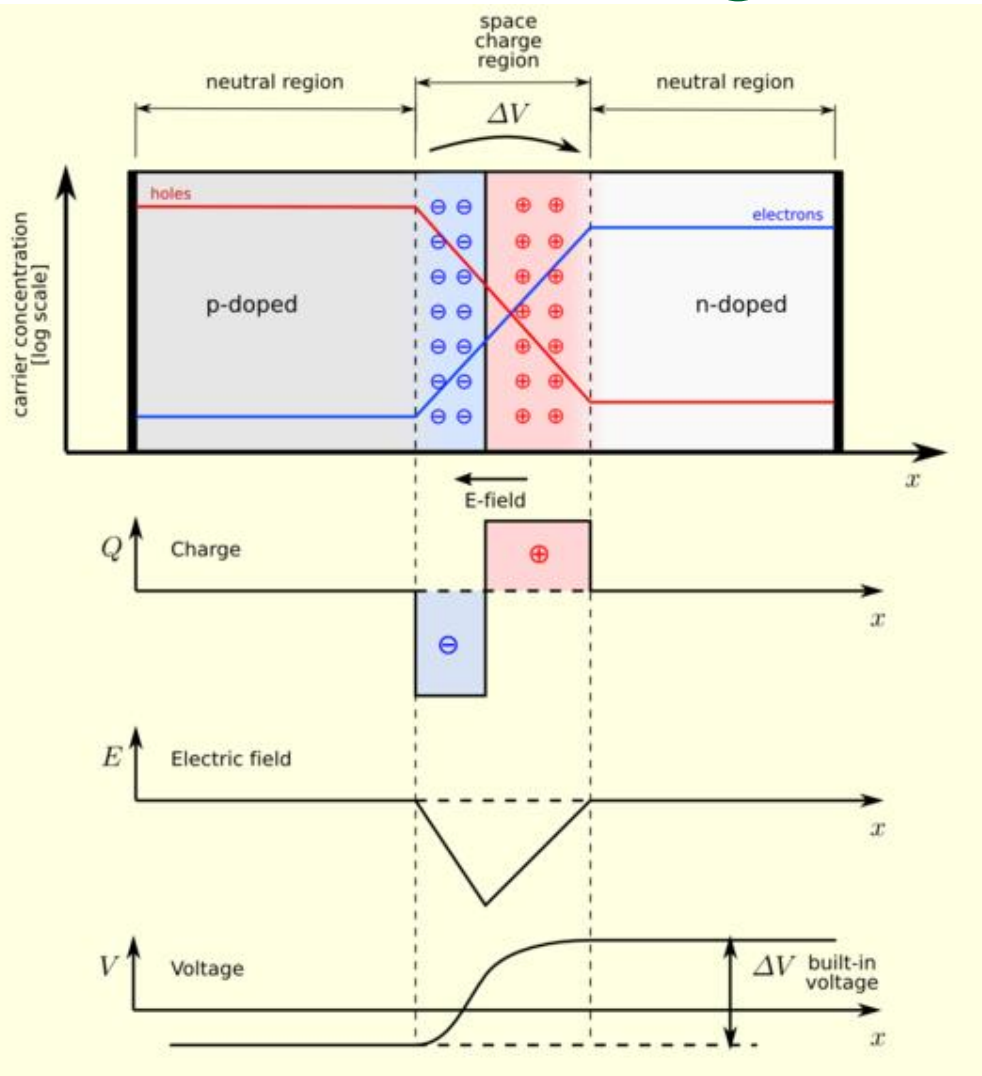


p-n junction



Energy bands at equilibrium

# Depletion Region



## Charge Neutrality

$$n + N_A^- w_P = p + N_D^+ w_N$$

Assuming:

full ionization,

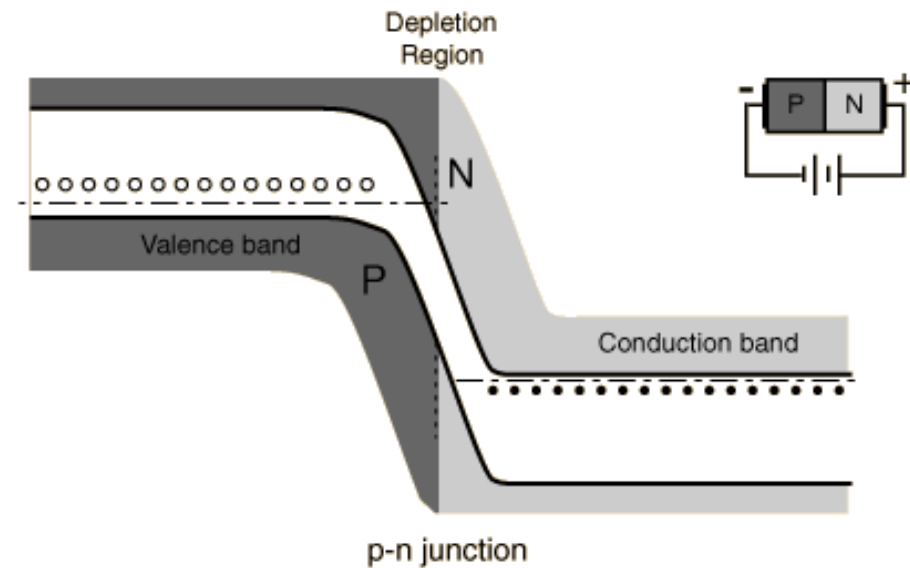
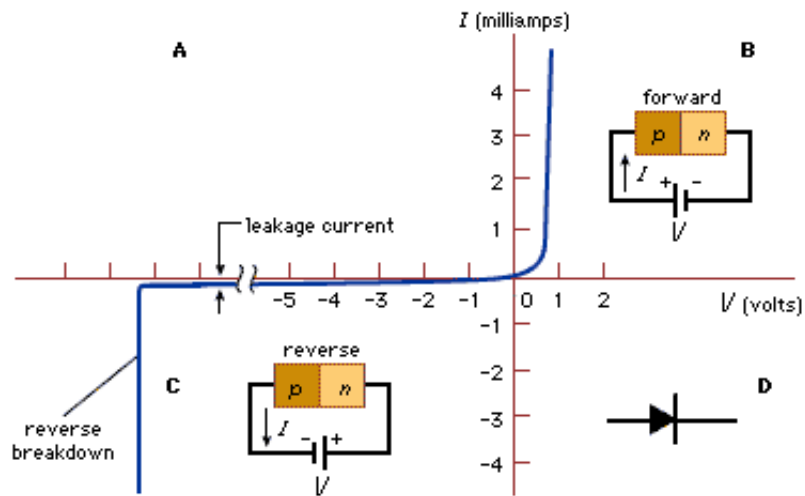
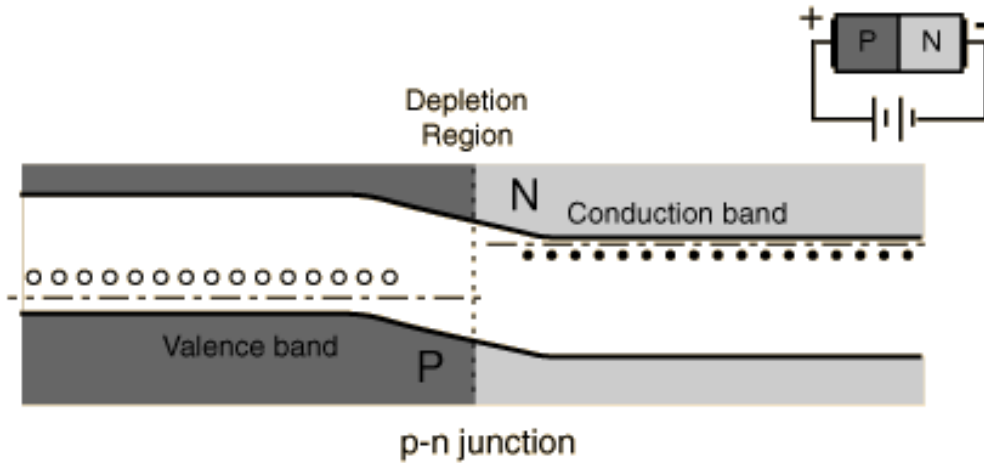
$$n, p \ll N_D, N_A$$

$$w = w_N + w_P$$

$$V_{bi} = \frac{kT}{q} \ln \left( \frac{N_A N_D}{p_0 n_0} \right)$$

$$W \approx \left[ \frac{2K_s \epsilon_0}{q} \left( \frac{N_A + N_D}{N_A N_D} \right) (V_{bi} - V) \right]^{\frac{1}{2}}$$

# Forward and Reverse Bias

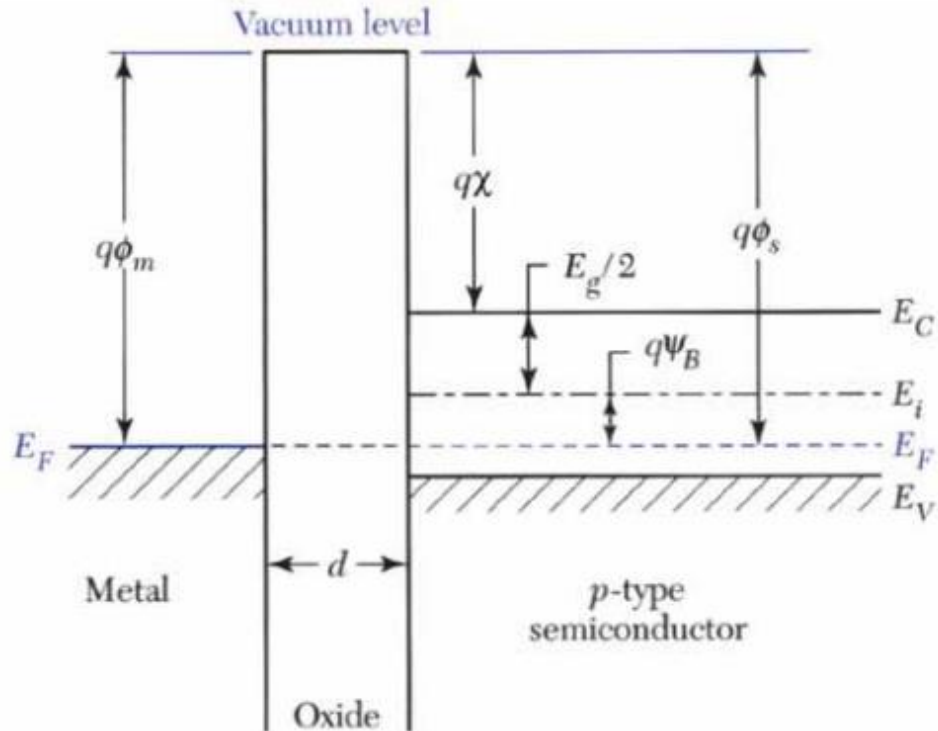


# Reverse current in p-n junctions

Contributions to the leakage current under reverse bias:

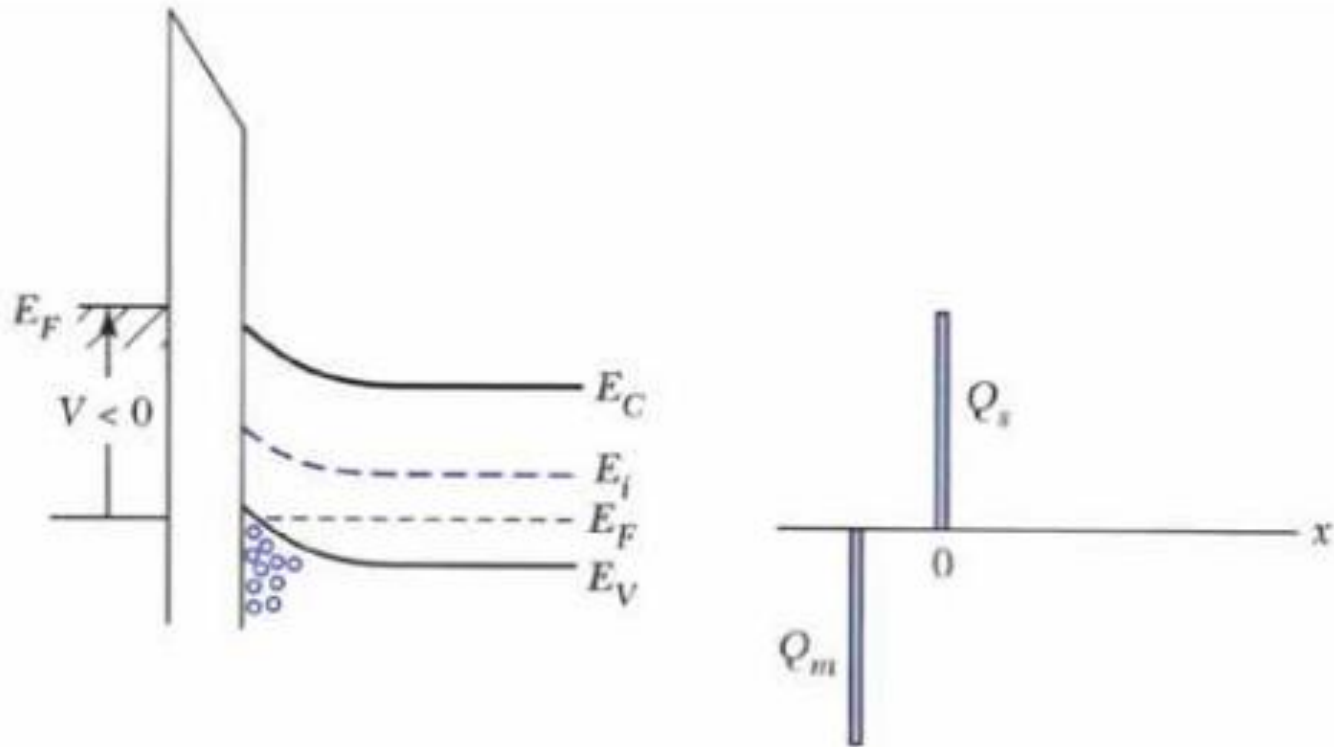
- diffusion current,  $J_{\text{diff}}$
- space charge generation current,  $J_{\text{gen}}$
- band-to-band tunneling current,  $J_{\text{tun}}$
- thermionic emission current (metals),  $J_{\text{them}}$
- gate-to-channel leakage (MOS),  $J_{\text{GOx}}$

# MOS Devices



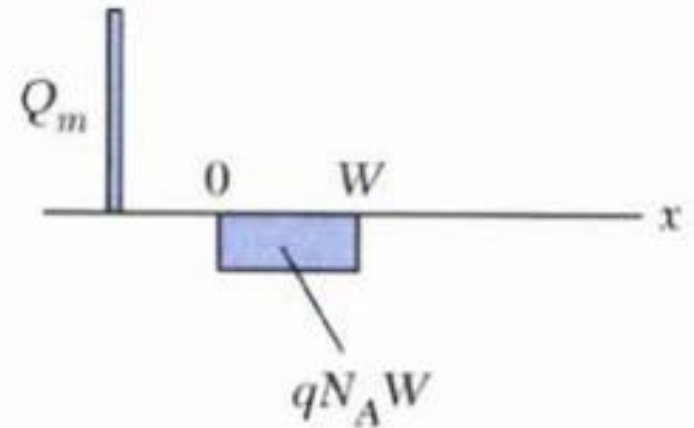
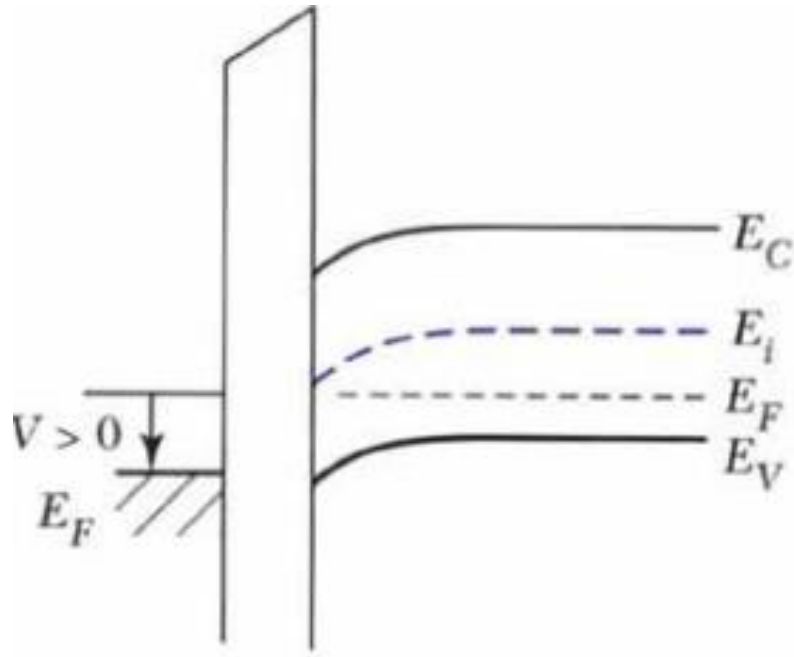
$$q\phi_{ms} \equiv (q\phi_m - q\phi_s) = q\phi_m - \left( q\chi + \frac{E_g}{2} + q\psi_B \right) = 0$$

# MOS - Accumulation



$$p_p = n_i e^{(E_i - E_F)/kT}$$

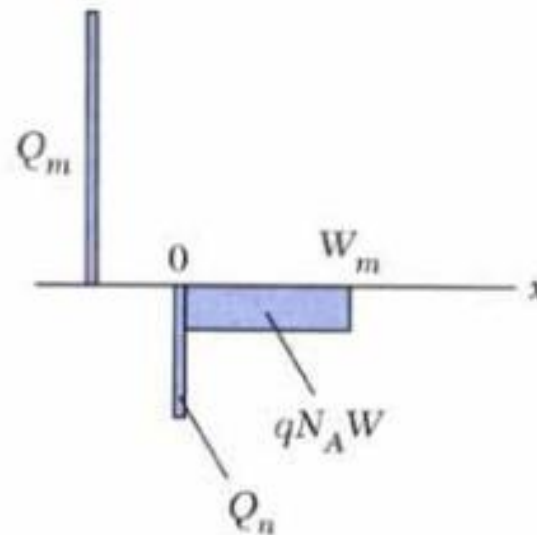
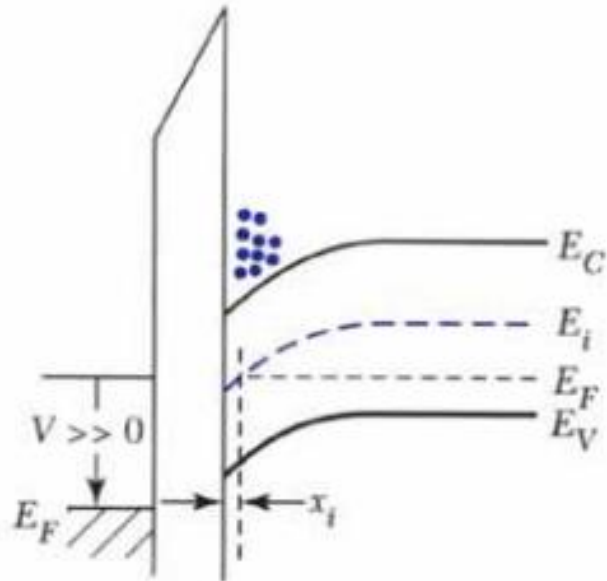
# MOS - Depletion



Charge Neutrality (Q on gate):  $Q = qN_A w$

$$E_m = Q/A\epsilon_0 = qN_A w/A\epsilon_0,$$

# MOS - Inversion

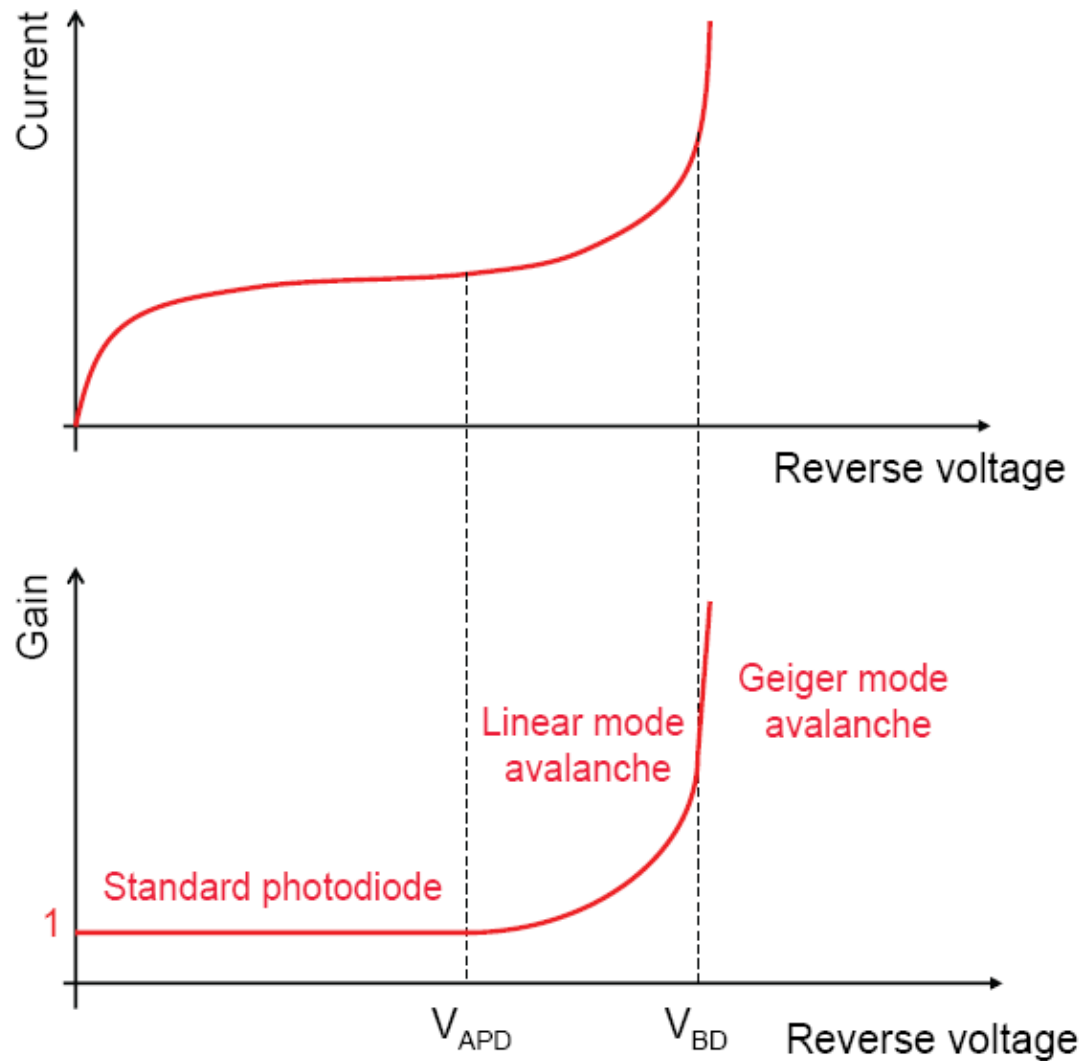


Minority carriers (electrons) accumulate:  $n_p = n_i e^{(E_F - E_i)/kT}$

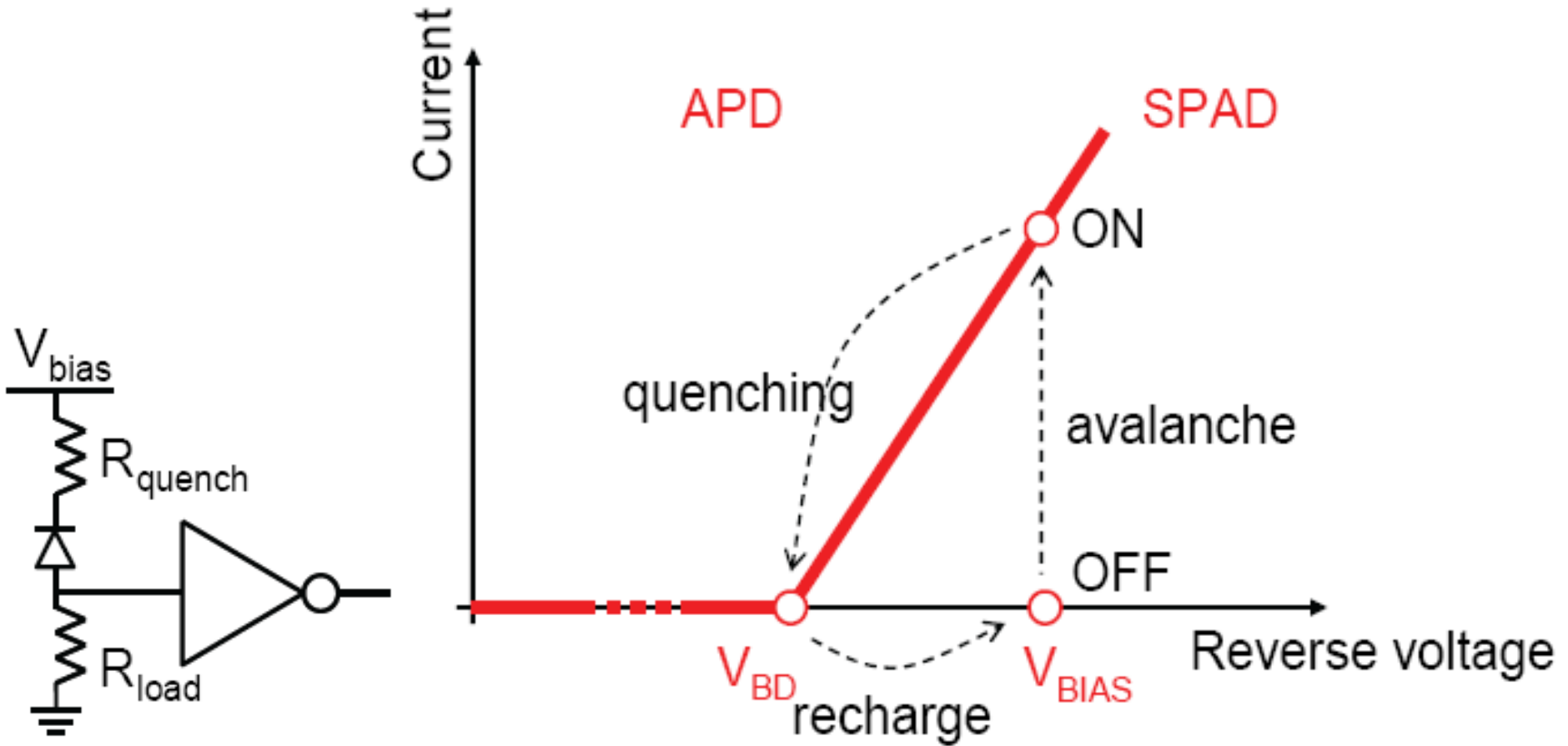
Depletion width at maximum.



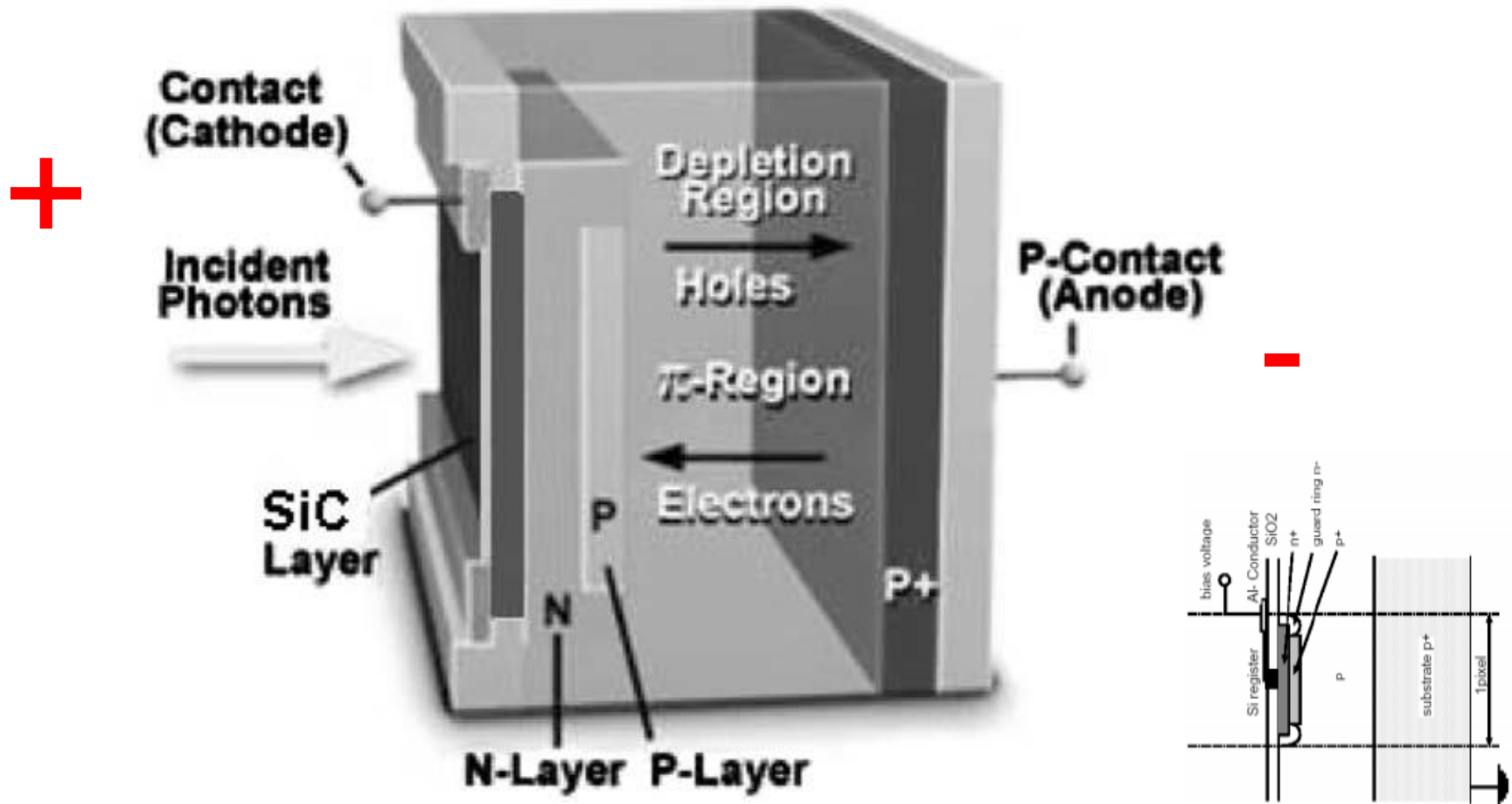
# Operation principle of APDs



# Quenching



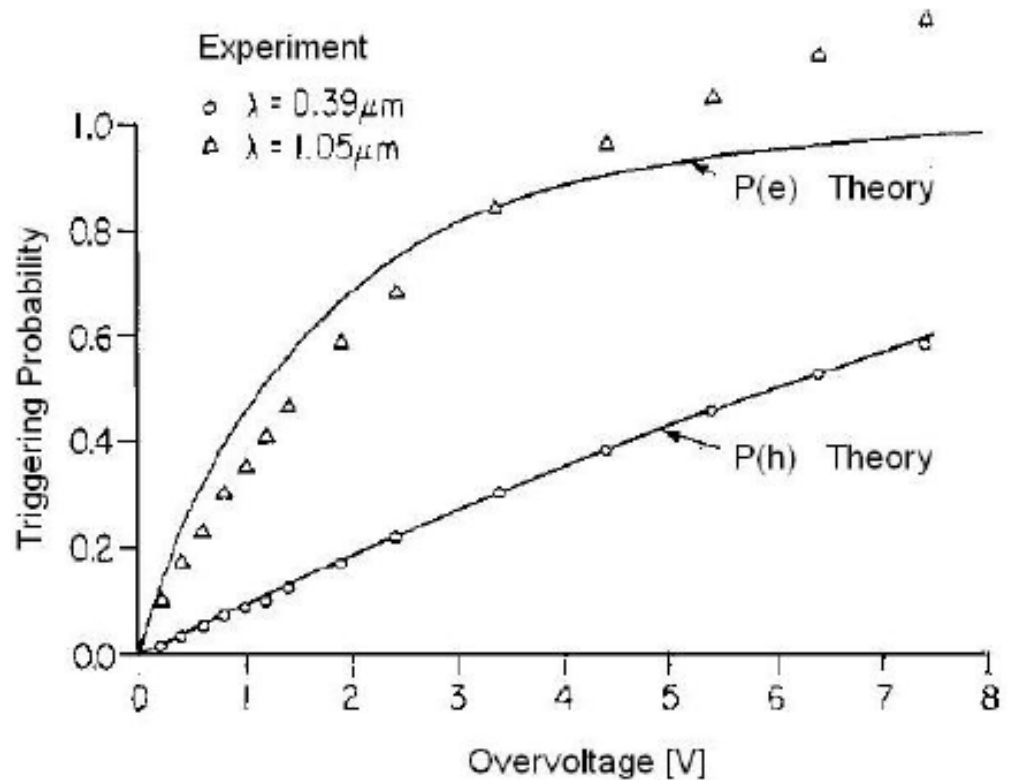
# Example of a Geiger-APD design



# Photon Detection Efficiency

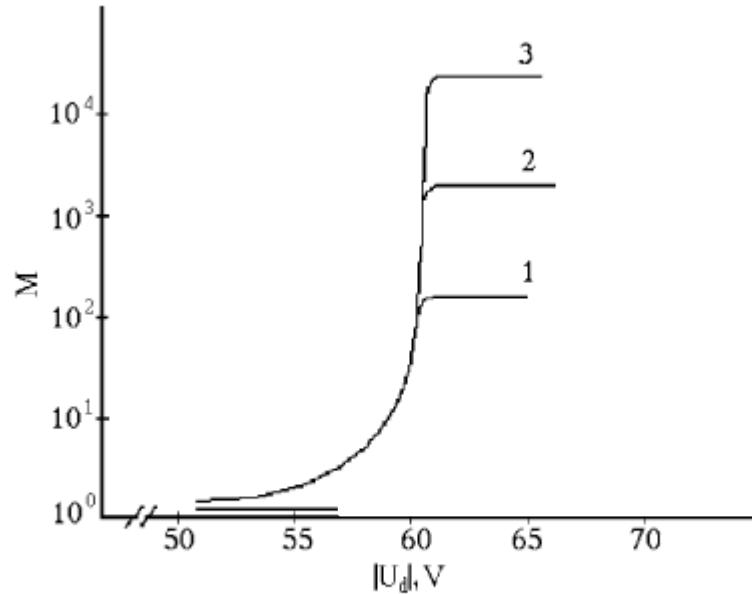
$$\text{PDE} = \text{QE} \varepsilon P_{\text{trigger}}$$

PDE - Photon Detection Efficiency  
 $\varepsilon$  - geometric fill factor  
QE - quantum efficiency

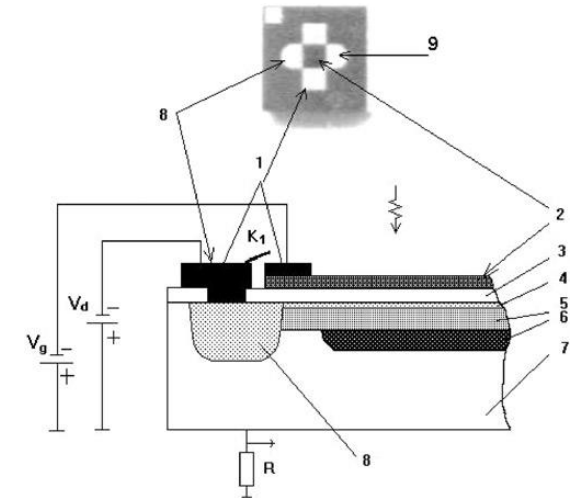


$$\text{QE} = \varepsilon_G(1 - R)(1 - e^{-\alpha x}),$$

# Gain



Photocurrent gain as a function of drain potential: 1 —  $V_g = -68.5$  V; 2 —  $V_g = -69.0$  V; 3 —  $V_g = -69.5$ ;



Structure of the basic element.

- 1 — thick Al electrodes;
- 2 — semitransparent Ti gate electrode;
- 3 — dielectric layer,  $\text{SiO}_2$ ;
- 4 —  $\text{p}^+$ -Si surface drift layer;
- 5 — p-Si layer;
- 6 —  $\text{n}^+$ -Si layer;
- 7 — n-Si wafer;
- 8 —  $\text{p}^+$ -Si drain;
- 9 —  $\text{p}^+$ -Si source.

$$A_i \sim C/q(V - V_b)$$

# Quenching

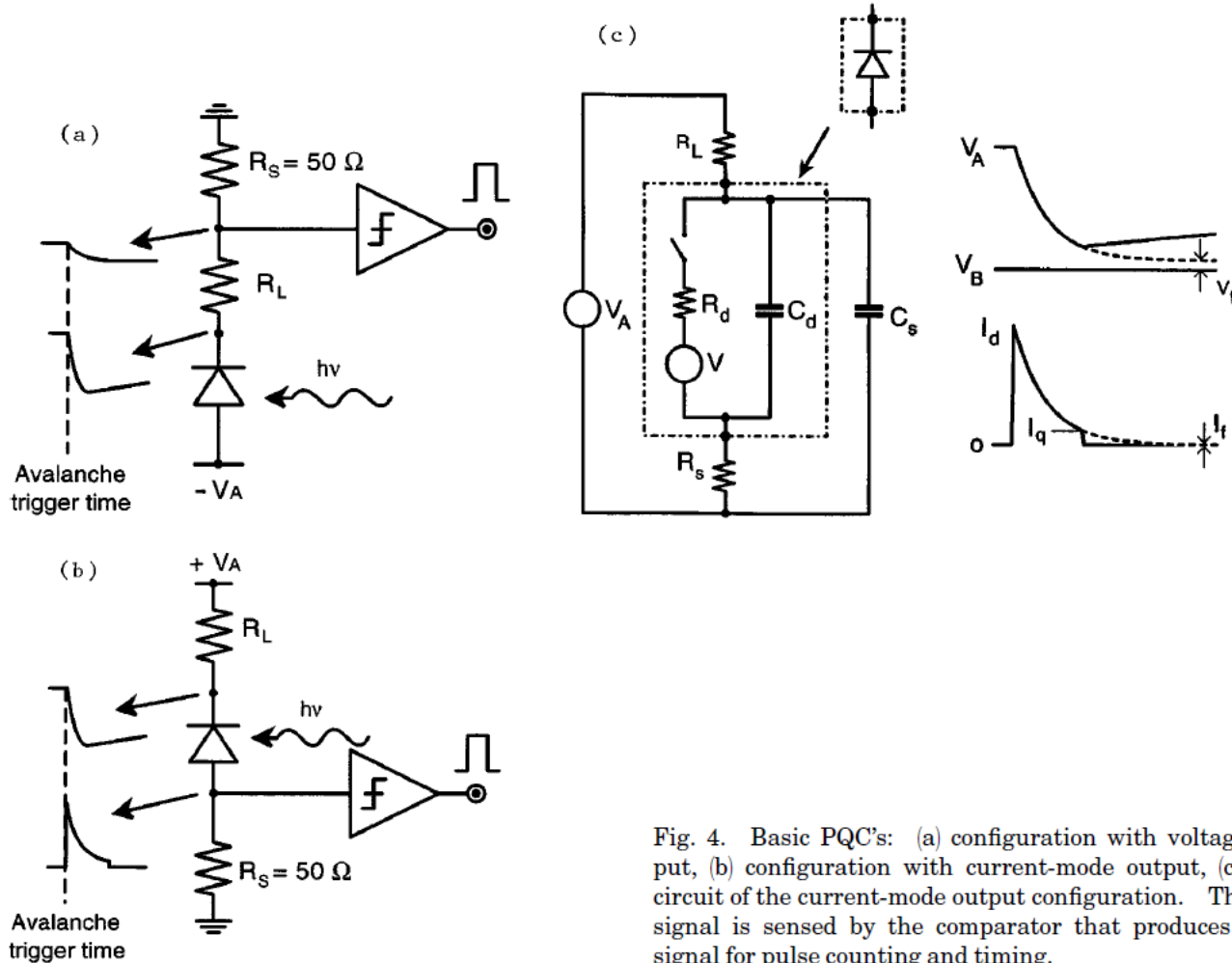


Fig. 4. Basic PQC's: (a) configuration with voltage-mode output, (b) configuration with current-mode output, (c) equivalent circuit of the current-mode output configuration. The avalanche signal is sensed by the comparator that produces a standard signal for pulse counting and timing.

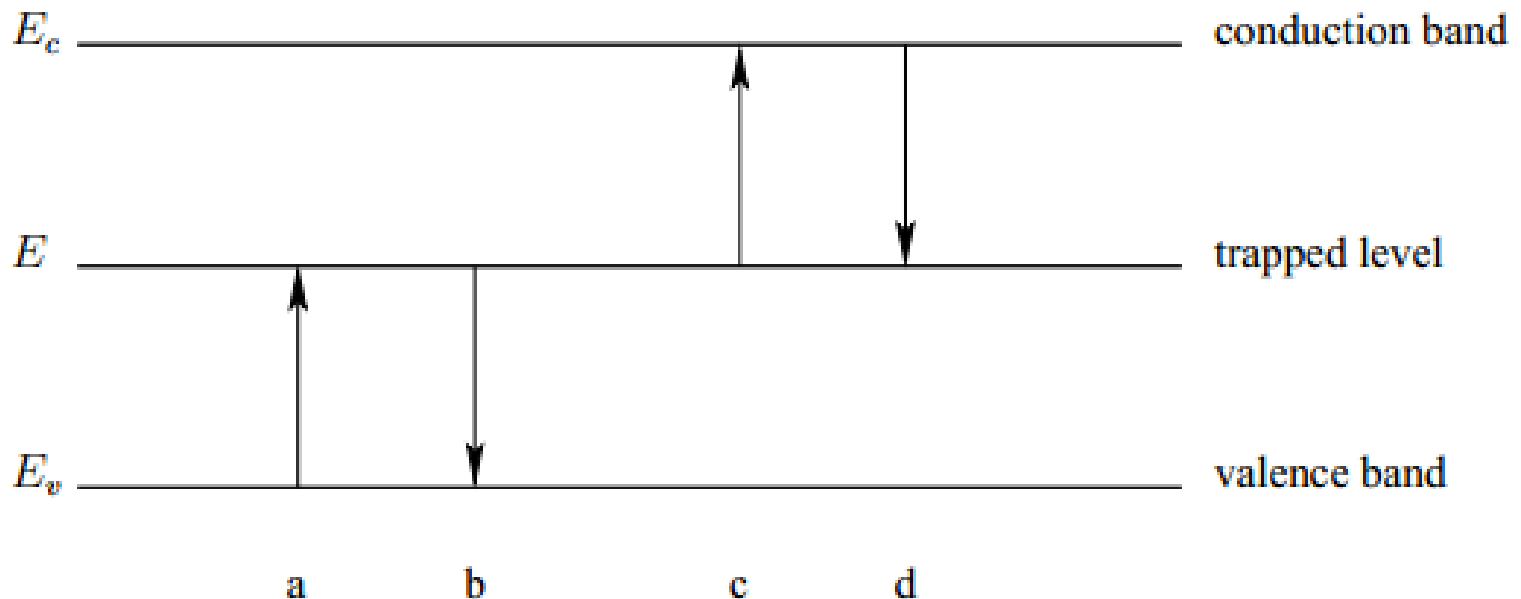
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# Dark Counts

- Main Causes:
    - thermally generated e-h pairs
    - diffusion from neutral regions
    - band to band tunnelling
    - release from charge traps (see also afterpulsing).
  - 100kHz to several MHz per mm<sup>2</sup> at 25
  - factor 2 reduction of the dark counts every 8–10 °C temperature decrease.
  - minimized by improving fabrication processes to reduce the number of generation-recombination centers (GR center), the impurities and crystal defects, which give rise to the Shockley-Read-Hall GR.
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# Shockley-Read-Hall GR

- Trap levels within the forbidden band caused by crystal impurities facilitates GR since the jump can be split into two parts



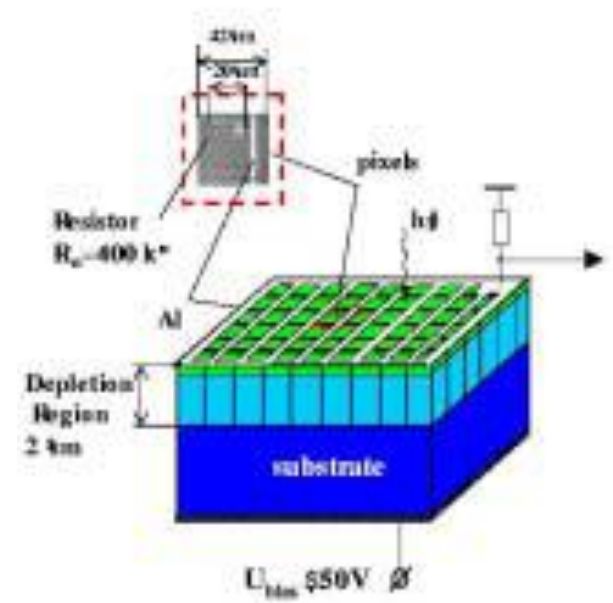
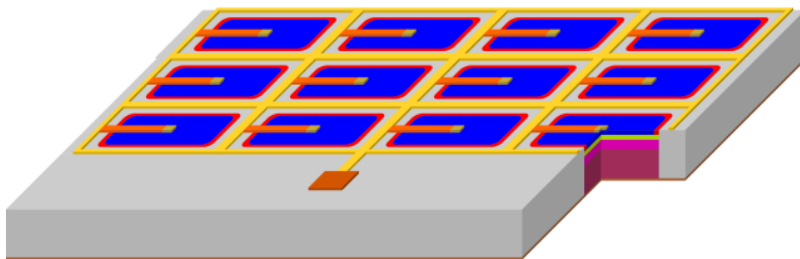
- (a) hole emission (an electron jumps from the valence band to the trapped level),  
(b) hole capture (an electron moves from an occupied trap to the valence band, a hole disappears),  
(c) electron emission (an electron jumps from trapped level to the conduction band),  
(d) electron capture (an electron moves from the conduction band to an unoccupied trap).



# SiPM

G-APDs can exhibit excellent single photon sensitivity in a wide spectral range with very short signal rise times but they lack proportional response to multi-photon events.

SiPM - multipixel G-APDs



~1000 pixels in small area (~1mm x 1mm)

# Silicon photomultiplier

## ■ Gain

- $M \sim 10^6$
- Stable w/ T

The change of the temperature and bias voltage needed for a gain variation of 1%

Photodetector	$\Delta T$	$\Delta V/V$
APD EG&G C30626E <sup>a</sup>	0.15°	$0.4V/400V = 10^{-3}$
APD Hamamatsu S5345 <sup>a</sup>	0.3°	$0.04V/300V = 1.5 \times 10^{-4}$
SiPM ( $M = 2 \times 10^6$ )	2.5°	$0.05V/50V = 10^{-3}$

## ■ Dark counts

<sup>a</sup> For the gain  $M = 100$  [5].

## ■ Optical crosstalk ( $\sim 3$ photons above $E_g$ )

## ■ Afterpulses

- Charge traps results in generation-recombination (GR) centres.
- High avalanche current increases the probability to fill the traps with carriers (deep traps  $\sim$  longer lifetimes).

# Trench separation of micro-cells

